

## EAST Search History

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
S95	0	ep-16460734.did.	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2008/09/01 15:12
S96	1	ep-1646073-\$ did.	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2008/09/01 15:12
S97	4	jp-2001085308-\$. did. or jp-05045605- \$ did. or jp- 200223408-\$ did.	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2008/09/01 15:31
S98	2	jp-08330212-\$ did.	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2008/09/01 15:31
S99	6	S97 or S98	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2008/09/01 15:32
S100	781	integrator with secondary near light near sources	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2008/09/01 15:41
S101	196920	(condenser near2 lens or condensing)	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2008/09/01 15:43
S102	577	S100 and S101	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2008/09/01 15:45
S103	12811	(mla or microlens near array or micro near lens near array)	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2008/09/01 15:50

S104	59	S102 and S103	US_PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2008/09/01 15:53
S105	3199	S101 same (overlap \$4 or superpos\$5 or superimpos\$5)	US_PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2008/09/01 16:14
S106	249	S100 and S105	US_PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2008/09/01 16:16
S107	155	S106 and 355/53,67,71.ccls.	US_PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2008/09/01 16:17
S108	1372070	(two or three or four or plural\$3 or multipl \$5) with (source or laser or light)	US_PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2008/09/01 16:28
S109	702	S108 and S100	US_PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2008/09/01 16:32
S110	248	S105 and S109	US_PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2008/09/01 16:33
S111	6309	laser near2 diode near array	US_PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2008/09/01 18:55
S112	683656	(\$5lithograph\$2 or (expos\$3 or imag\$3 or pattern\$3) near5 (wafer or substrate or workpiece or work near piece))	US_PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2008/09/01 18:56
S113	1644	S111 and S112	US_PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2008/09/01 18:56

S114	781	integrator with secondary near light near sources	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2008/09/01 18:57
S115	0	S113 and S114	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2008/09/01 18:57
S116	84	S113 and integrator and condens\$3	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2008/09/01 18:58

9/2/08 6:56:44 AM

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